**Amendments to the Claims:**

This listing of claims will replace all prior versions, and listings, of claims in the application:

**Listing of Claims:**

1. (Original) A method of producing an oxide superconducting film on a single-crystal substrate by depositing, on the single-crystal substrate, substances scattered from a raw material due to irradiation with laser beams according to a pulsed-laser deposition method, wherein the irradiation of the raw material is performed in a manner such that the repetition frequency of the pulse irradiation of the laser beams is divided into at least two steps.

2. (Original) A method of producing an oxide superconducting film according to claim 1, wherein the laser frequency of a first step is smaller than the laser frequency of a second step.

3. (Currently Amended) A method of producing an oxide superconducting film according to claim 1 [[or 2]], wherein the laser power is 400 mJ or more.

4. (Currently Amended) A method of producing an oxide superconducting film according to ~~any one of claims 1 or 2~~ claim 1, wherein the temperature of the single-crystal substrate during the pulsed-laser deposition is more than or equal to 600°C and less than 1,200°C.

5. (Currently Amended) A method of producing an oxide superconducting film according to claim 3 ~~any one of claims 1 to 4~~, wherein the ~~gas pressure~~ temperature of the single-crystal substrate during the pulsed-laser deposition is more than or equal to 600°C and less than 1,200°C.

6. (Currently Amended) A method of producing an oxide superconducting film according to ~~any one of claims 1 to 4~~ claim 1, wherein the gas pressure during the pulsed-laser deposition is within the range of 1.33 Pa to 66.66 Pa.

7. (Currently Amended) A method of producing an oxide superconducting film according to ~~any one of claims 1 to 6~~ claim 3, wherein the ~~atmosphere~~ gas pressure during the pulsed-laser deposition ~~contains oxygen~~ is within the range of 1.33 Pa to 100 Pa.

8. (Currently Amended) A method of producing an oxide superconducting film according to ~~any one of claims 1 to 7~~ claim 4, wherein the gas pressure during the pulsed-laser deposition is within the range of 1.33 Pa to 100 Pa ~~oxide superconducting film comprises an RE123 composition, where RE is composed of at least one of a rare-earth element and yttrium~~.

9. (New) A method of producing an oxide superconducting film according to claim 1, wherein the gas pressure during the pulsed-laser deposition is within the range of 1.33 Pa to 66.66 Pa.

10. (New) A method of producing an oxide superconducting film according to claim 3, wherein the gas pressure during the pulsed-laser deposition is within the range of 1.33 Pa to 66.66 Pa.

11. (New) A method of producing an oxide superconducting film according to claim 4, wherein the gas pressure during the pulsed-laser deposition is within the range of 1.33 Pa to 66.66 Pa.

12. (New) A method of producing an oxide superconducting film according to claim 1, wherein the atmosphere during the pulsed-laser deposition contains oxygen.

13. (New) A method of producing an oxide superconducting film according to claim 3, wherein the atmosphere during the pulsed-laser deposition contains oxygen.

14. (New) A method of producing an oxide superconducting film according to claim 4, wherein the atmosphere during the pulsed-laser deposition contains oxygen.

15. (New) A method of producing an oxide superconducting film according to claim 6, wherein the atmosphere during the pulsed-laser deposition contains oxygen.

16. (New) A method of producing an oxide superconducting film according to claim 1, wherein the oxide superconducting film comprises an RE123 composition, where RE is composed of at least one of a rare-earth element and yttrium.

17. (New) A method of producing an oxide superconducting film according to claim 3, wherein the oxide superconducting film comprises an RE123 composition, where RE is composed of at least one of a rare-earth element and yttrium.

18. (New) A method of producing an oxide superconducting film according to claim 4, wherein the oxide superconducting film comprises an RE123 composition, where RE is composed of at least one of a rare-earth element and yttrium.

19. (New) A method of producing an oxide superconducting film according to claim 6, wherein the oxide superconducting film comprises an RE123 composition, where RE is composed of at least one of a rare-earth element and yttrium.

20. (New) A method of producing an oxide superconducting film according to claim 12, wherein the oxide superconducting film comprises an RE123 composition, where RE is composed of at least one of a rare-earth element and yttrium.